

## Supporting Information

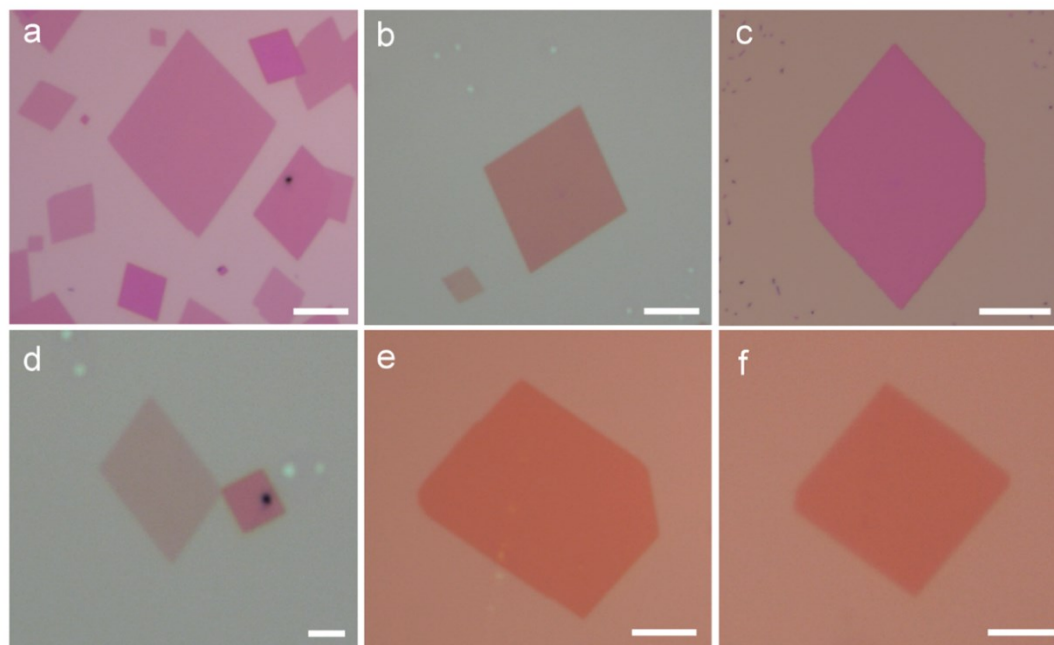
### The intrinsic hydrogen evolution performance of 2D molybdenum carbide

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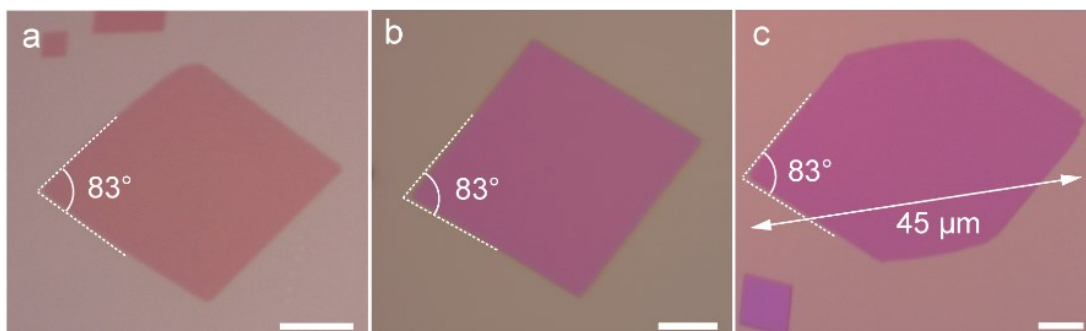
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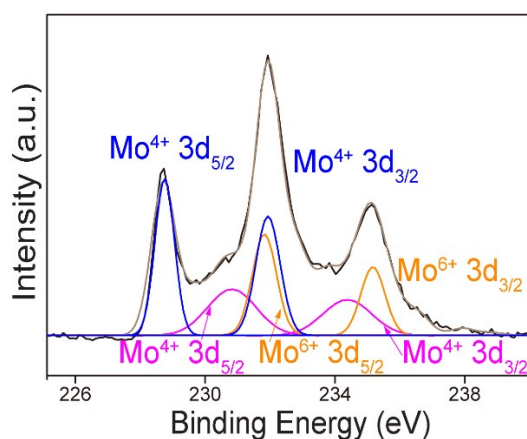
<sup>c</sup>. Fujian Provincial Key Laboratory of Nanomaterials, Fujian Institute of Research on the Structure of Matter, Chinese Academy of Sciences, Fuzhou, 350002, China



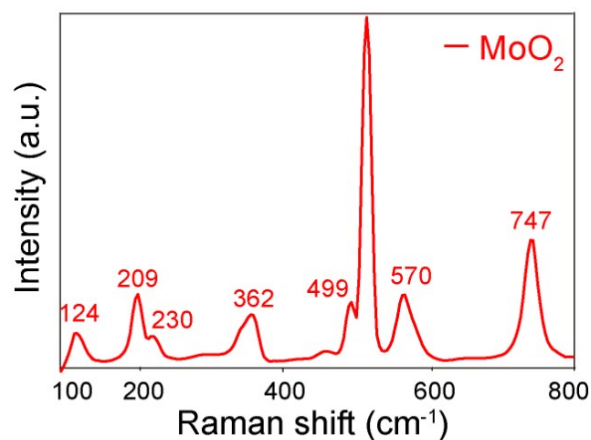
**Figure S1.** OM images of MoO<sub>2</sub> crystals with different shapes. (a) OM image of rhombic and parallelogram-type and pentagonal MoO<sub>2</sub> flakes, (b) rhombus, (c) hexagon, (d) parallelogram, (e) pentagon, and (f) rectangle. Scale bars are 10 μm.



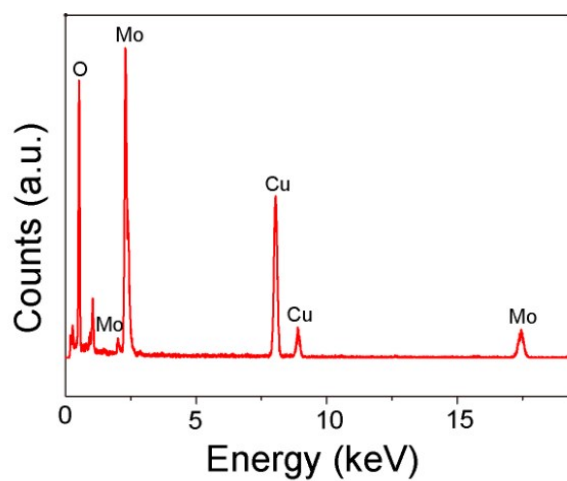
**Figure S2.** Thickness tunable growth of 2D MoO<sub>2</sub> crystals with varying growth temperature. (a–c) Optical microscopy (OM) images of rhombic and hexagonal MoO<sub>2</sub> flakes on the SiO<sub>2</sub>/Si substrate at increasing temperatures of ~790°C, ~810°C, ~830 °C, respectively. The acute angle of rhombic and hexagonal MoO<sub>2</sub> flakes is 83°. Scale bars: 5 μm.



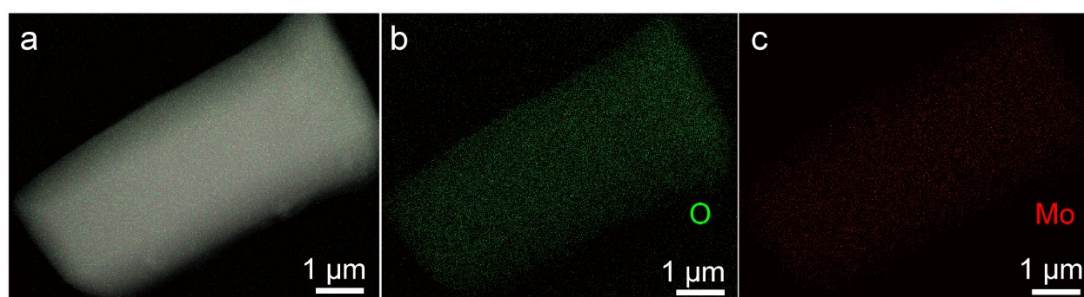
**Figure S3.** XPS results of Mo 3d regions of the synthesized MoO<sub>2</sub> flakes.



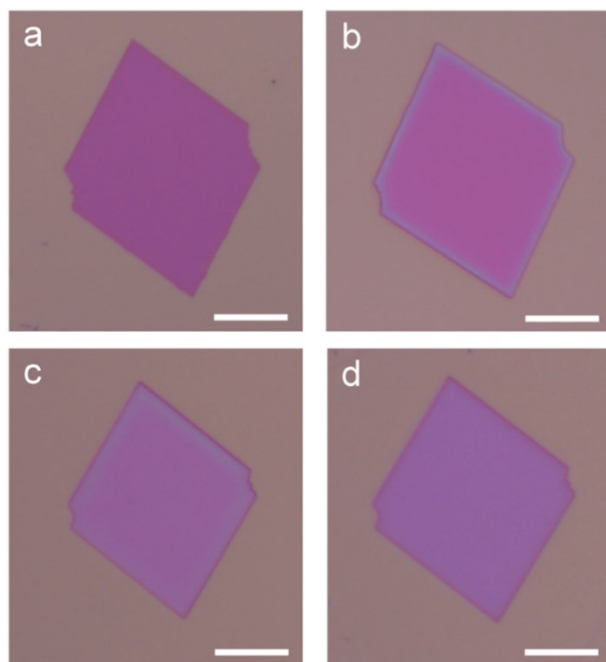
**Figure S4.** Raman spectra of the synthesized MoO<sub>2</sub> flakes.



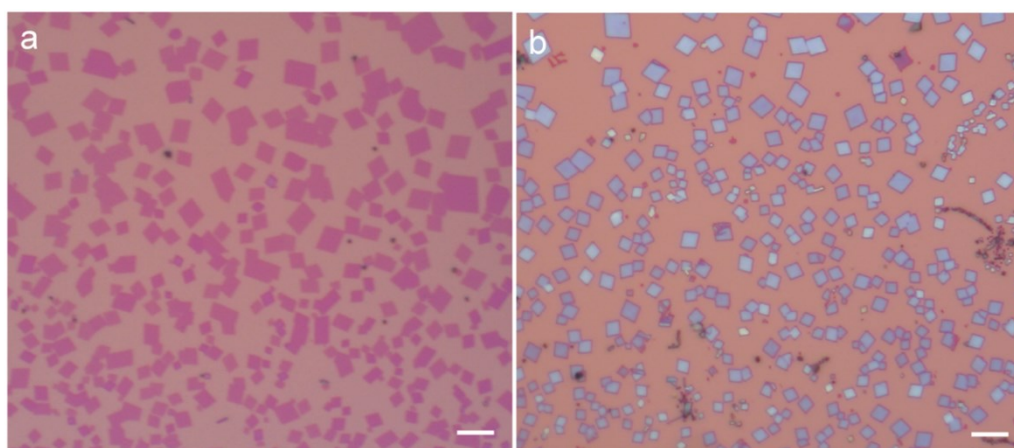
**Figure S5.** The energy dispersive spectrometry (EDS) analysis of the synthesized MoO<sub>2</sub> flakes.



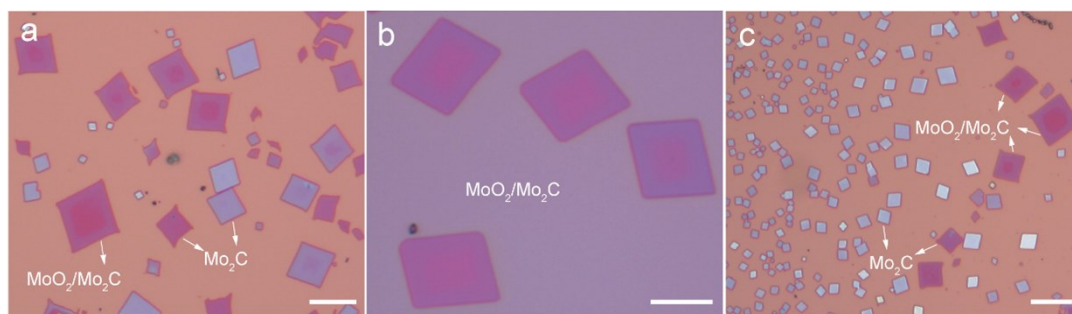
**Figure S6.** (a) High-angle annular dark-field scanning transmission electron microscopy image of a MoO<sub>2</sub> flake. (b, c) EDS mapping images of O and Mo for a MoO<sub>2</sub> flake achieved on a STEM grid, respectively.



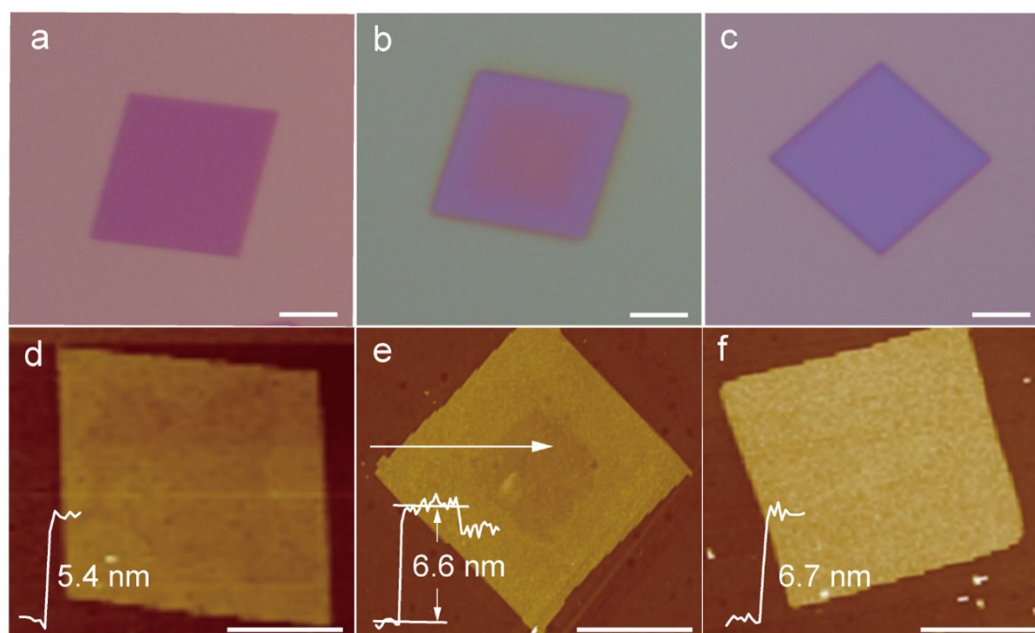
**Figure S7.** (a) Optical microscopy (OM) image of hexagonal MoO<sub>2</sub> flakes on the SiO<sub>2</sub>/Si substrate. (b) OM images of the MoO<sub>2</sub>/Mo<sub>2</sub>C lateral hybrid structure and Mo<sub>2</sub>C flakes grown at increasing carbonization time of ~10 min, ~15 min, ~40 min, respectively. The Mo<sub>2</sub>C ratio of b, c and d is approximate ~15%, ~35%, ~100%, respectively. Red, pink regions correspond to MoO<sub>2</sub>, Mo<sub>2</sub>C, respectively. Scale bars: 5  $\mu\text{m}$ .



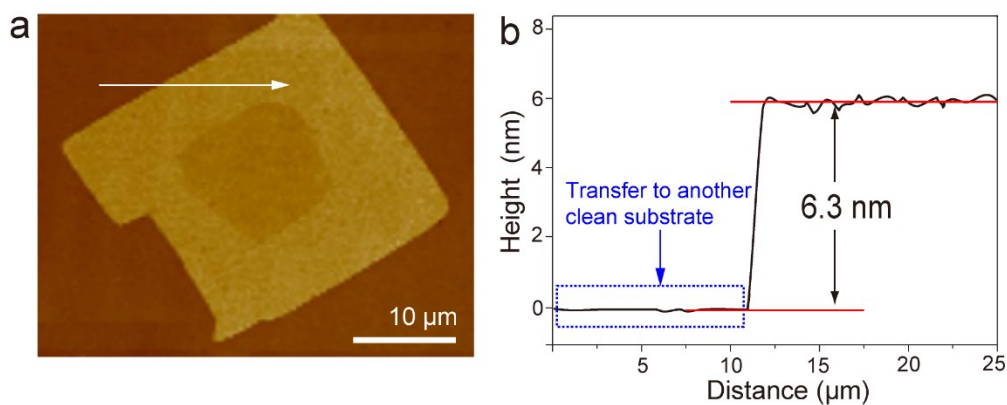
**Figure S8.** (a) Optical microscopy (OM) image of MoO<sub>2</sub> flakes on the SiO<sub>2</sub>/Si substrate. (b) Optical microscopy (OM) image of the Mo<sub>2</sub>C flakes on the SiO<sub>2</sub>/Si substrate. Scale bars: 10  $\mu\text{m}$ .



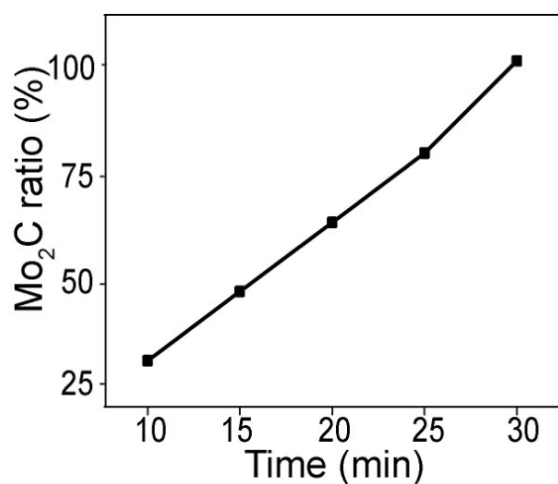
**Figure S9.** (a-c) Optical microscopy (OM) image of MoO<sub>2</sub>/Mo<sub>2</sub>C lateral hybrid structure and Mo<sub>2</sub>C flakes grown at increasing carbonization time of ~15 min. The smaller the lateral dimension of MoO<sub>2</sub> flakes, the easier it is to be carbonized. Scale bars: 10 μm.



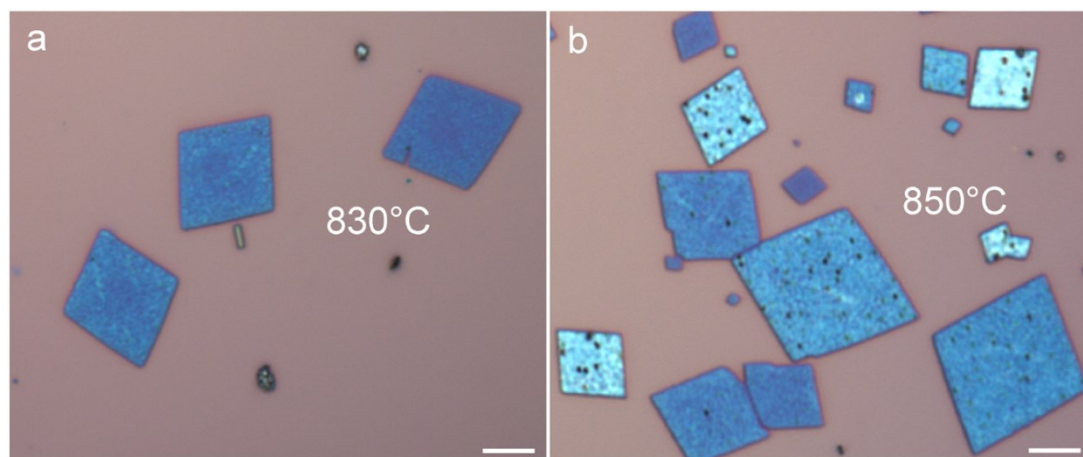
**Figure S10.** (a-c) Optical microscopy (OM) images of MoO<sub>2</sub>, MoO<sub>2</sub>/Mo<sub>2</sub>C lateral hybrid structure and fully converted Mo<sub>2</sub>C flakes on the SiO<sub>2</sub>/Si substrate. (d) The corresponding atomic force microscopy (AFM) image of MoO<sub>2</sub> flake in (b). (e) AFM image of MoO<sub>2</sub>/Mo<sub>2</sub>C lateral hybrid structure in (c). Inset is the height profile along the white arrow. (f) AFM image of fully converted α-Mo<sub>2</sub>C flake in (d). Scale bars: 5 μm.



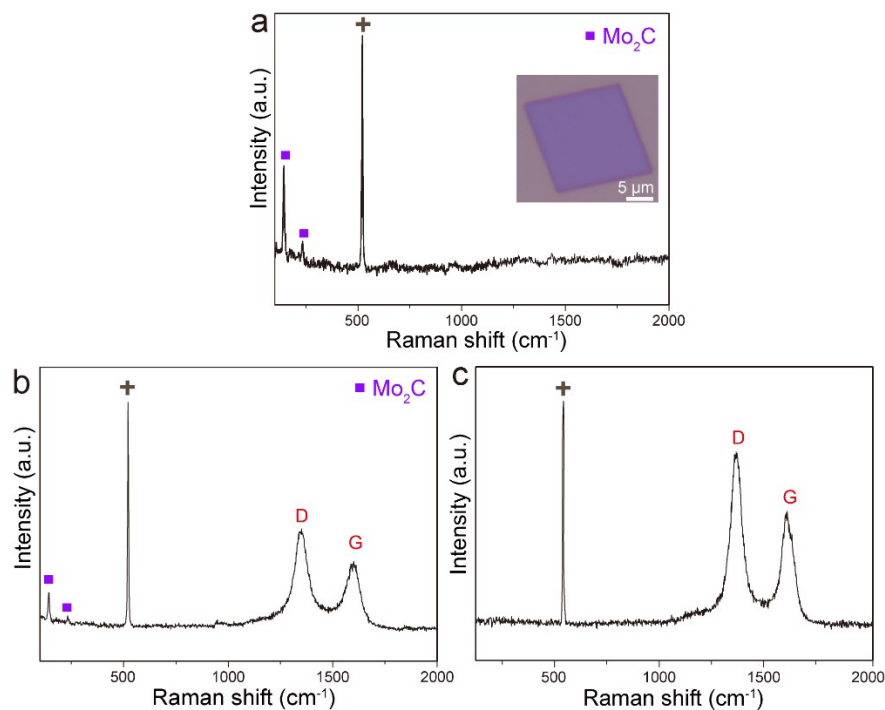
**Figure S11.** (a) OM image of the MoO<sub>2</sub>/Mo<sub>2</sub>C lateral hybrid structure is transferred to another clean SiO<sub>2</sub>/Si substrate to eliminate the influence of the roughness of the SiO<sub>2</sub>/Si substrate. (b) The corresponding height profile along the white arrow in (a).



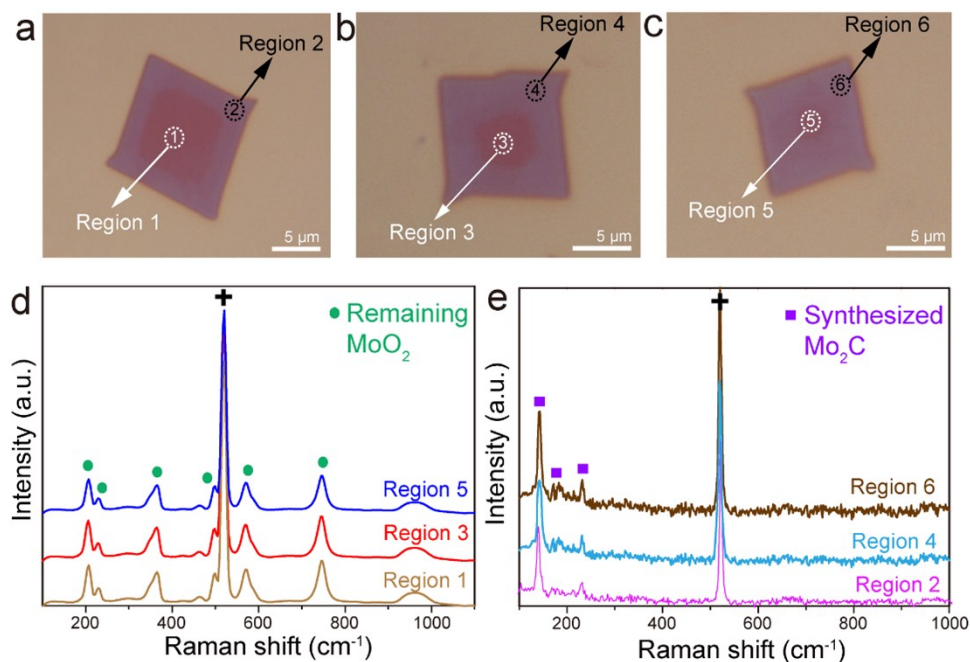
**Figure S12.** The ratio of Mo<sub>2</sub>C at different thermal annealing time.



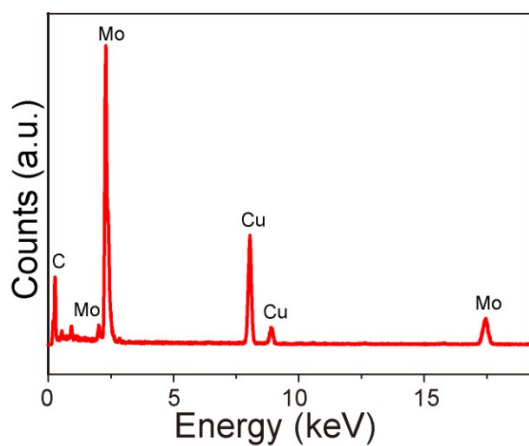
**Figure S13.** (a,b) OM images of the Mo<sub>2</sub>C flakes synthesized at 830 °C and 850 °C, respectively, showing rough surfaces and substantial morphological degradation.



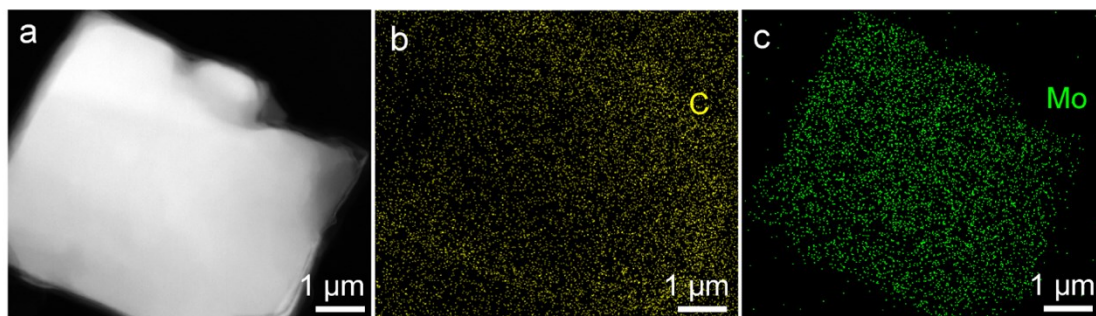
**Figure S14.** (a-c) Raman spectra of the synthesized  $\text{Mo}_2\text{C}$  at increasing carbonization time of  $\sim 40$  min,  $\sim 50$  min,  $\sim 60$  min, respectively (Carbonization temperature is  $800^\circ\text{C}$ ). Inset in (a): The corresponding OM image of the  $\text{Mo}_2\text{C}$  flake. When the calcination time is  $\sim 40$  min at  $800^\circ\text{C}$ , no other peaks are observed from the wide range of Raman shifts, such as the D ( $\sim 1350\text{ cm}^{-1}$ ) or G ( $\sim 1595\text{ cm}^{-1}$ ) mode of graphitic carbon. As the calcination time increases, two distinct D and G modes peaks are observed. The grey cross represents the Raman peak of Si.



**Figure S15.** (a-c) OM images of MoO<sub>2</sub>/Mo<sub>2</sub>C lateral hybrid structure. The corresponding Mo<sub>2</sub>C to initial MoO<sub>2</sub> size ratio is approximately 50%, 65%, 80%, respectively. (d, e) The corresponding Raman Spectra of the remaining MoO<sub>2</sub> and the synthesized Mo<sub>2</sub>C in (a-c). The black cross represents the Raman peak of Si.

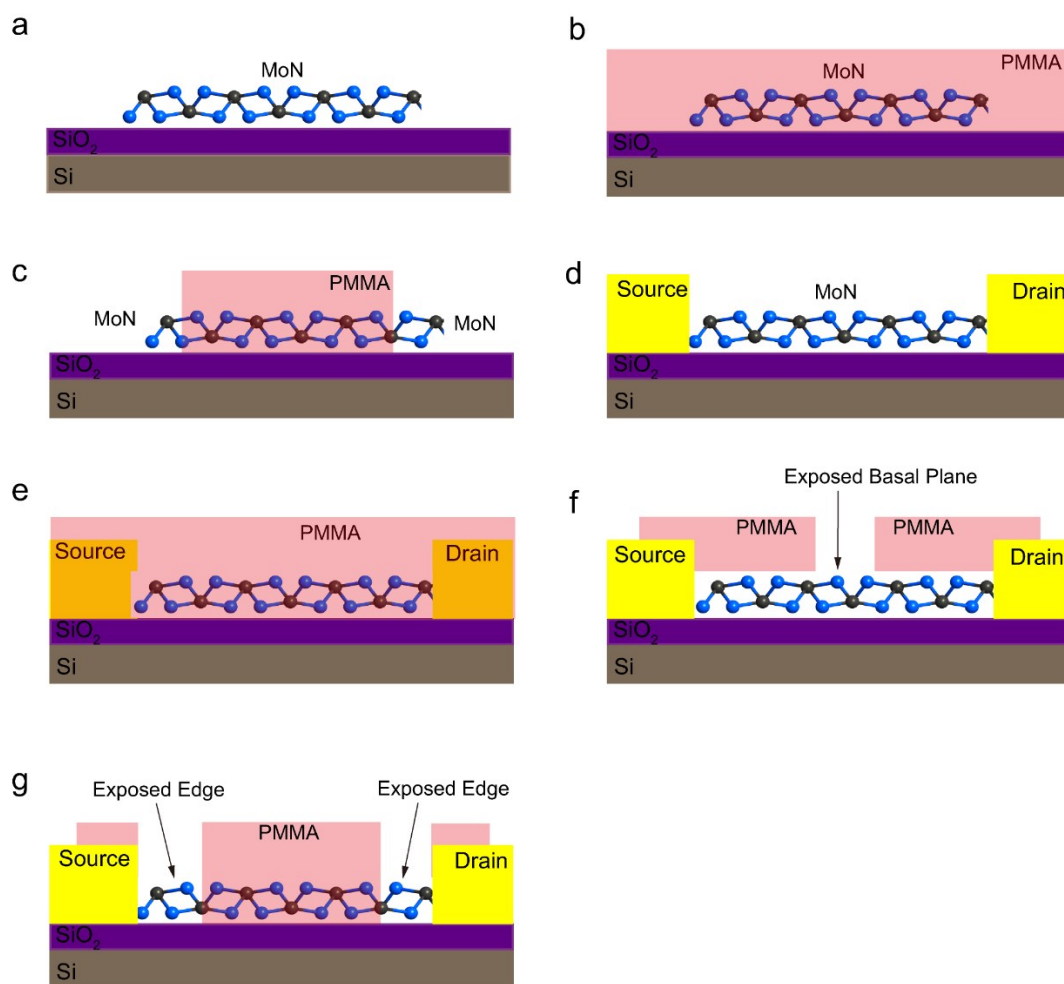


**Figure S16.** The EDS analysis of the Mo<sub>2</sub>C flakes synthesized on the SiO<sub>2</sub>/Si substrate.

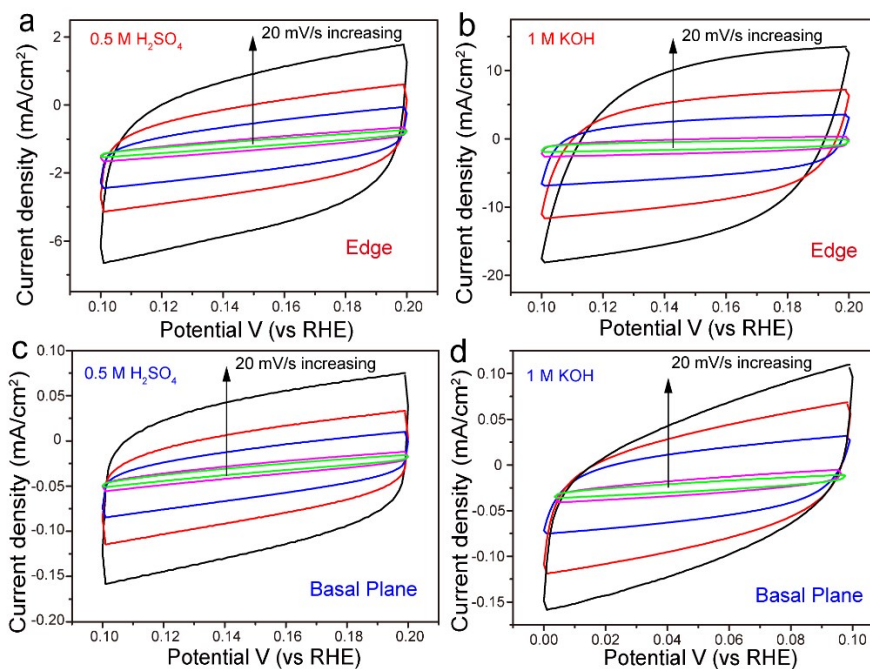




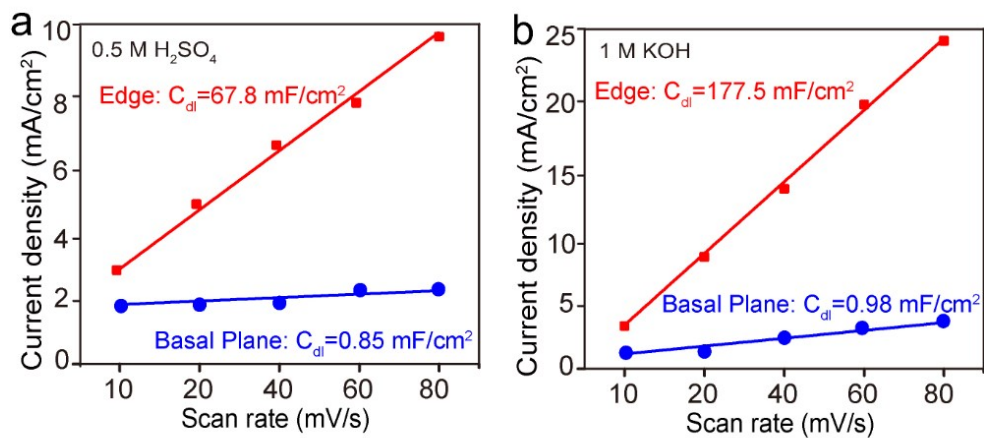
**Figure S17.** (a) High-angle annular dark-field scanning transmission electron microscopy image of a Mo<sub>2</sub>C flake. (b, c) EDS mapping images of C and Mo for a Mo<sub>2</sub>C flake achieved on a STEM grid, respectively.



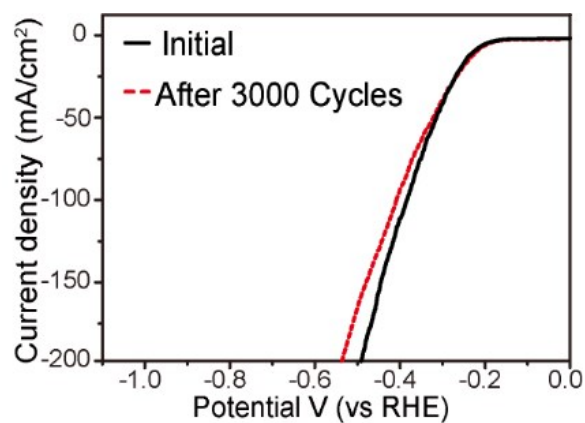
**Figure S18.** Illustrations displaying the EBL manufacture processes of electrochemical microcell devices setup. (a) The Mo<sub>2</sub>C flakes are transferred on the SiO<sub>2</sub>/Si substrate. (b) SiO<sub>2</sub>/Si substrate was covered with PMMA. (c) Electrodes patterns are defined by EBL. (d) Cr/Au electrodes deposited to contact selected individual nanosheets via thermal evaporation. (e) The microcell setup is covered with PMMA again. (f,g) Finally step of EBL to define windows on (f) only the exposed basal plane (while covering the edges) or (g) only the exposed edges (while covering the basal plane) and electrodes.



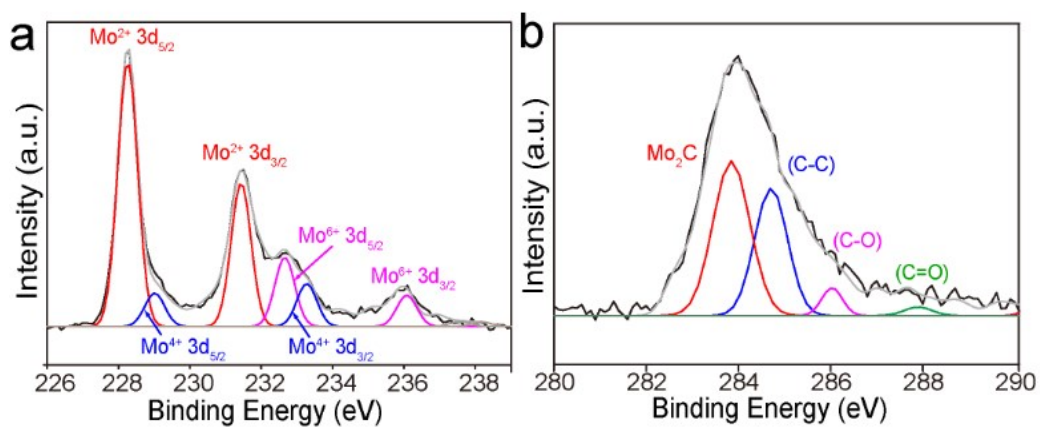
**Figure S19.** (a-d) Electrochemical cyclic voltammetry (CV) tests on edge and basal plane of Mo<sub>2</sub>C with different rates from 10 to 80 mV/s in the potential range of 0.10 ~ 0.20 V in 0.5 M H<sub>2</sub>SO<sub>4</sub> and 1 M KOH.



**Figure S20.** (a, b)  $C_{dl}$  measurements for determining electrochemically active surface areas of basal plane and edge of Mo<sub>2</sub>C in 0.5 M H<sub>2</sub>SO<sub>4</sub> and 1 M KOH.



**Figure S21.** Long-term stability test for the 2D Mo<sub>2</sub>C nanosheet. The polarization curves were recorded at a scan rate of 5 mV s<sup>-1</sup> after 3000 potential cycles in 1 M KOH.



**Figure S22.** XPS spectra of (a) Mo 3d, (b) C 1s for 2D Mo<sub>2</sub>C nanosheet after stability test for HER.

**Table S1.** A comparison of the HER parameters of the 2D Mo<sub>2</sub>C in this work with various 2D samples and other state-of-the-art Mo<sub>2</sub>C-based catalysts.

Materials	Substrates	Electrolytes	$\eta$ (mV) ( $j=10$ mA/cm <sup>2</sup> )	Tafel Slope (mV/dec)	Active Site	Ref.
Mo <sub>2</sub> C	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	281	54.4	Edge	This work
		1.0 M KOH	168	35.2		
1T-MoS <sub>2</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~200	~40	Edge oxidation	1
1T-MoS <sub>2</sub>	graphite	0.5 M H <sub>2</sub> SO <sub>4</sub>	187	43	Edge	2
Monolayer 2H-MoS <sub>2</sub>	Au	0.5 M H <sub>2</sub> SO <sub>4</sub>	170	60	S-vacancy and strain	3
3Co <sub>Mo</sub> -V <sub>s</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	75	57	in-plane domain	4
MoS <sub>2</sub> /graphene	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~200	54	grain boundaries	5
Mo SAs/ML-MoS <sub>2</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~107	36.4	unsaturate-d Mo SAs	6
		1.0 M KOH	~209	35.1		
Monolayer MoS <sub>2</sub>	Glass carbon (GC)	0.5 M H <sub>2</sub> SO <sub>4</sub>	—	~140	Edge	7
Monolayer MoS <sub>2</sub>	Au	0.5 M H <sub>2</sub> SO <sub>4</sub>	~200	61-74	Edge	8
1T'-MoS <sub>2</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~180	100	1T' phase	9
2H-MoS <sub>2</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~230	~50	Sulfur vacancies	10
Monolayer 2H-MoS <sub>2</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~430	~116	Edge	11
Monolayer 1T'-MoS <sub>2</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~355	~56	1T' phase	11
Monolayer 2H-MoS <sub>2</sub>	Au	0.5 M H <sub>2</sub> SO <sub>4</sub>	—	55	Edge	12
Monolayer MoS <sub>2-x</sub> O <sub>x</sub>	Au	0.5 M H <sub>2</sub> SO <sub>4</sub>	~260	67	Oxidized basal plane	13
Re <sub>0.55</sub> Mo <sub>0.45</sub> S <sub>2</sub>	GC	0.5 M H <sub>2</sub> SO <sub>4</sub>	~170	56	Re-doped	14
V <sub>Re</sub> -ReS <sub>2</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	147	69	Re vacancy	15
1T-SnS <sub>2</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~450	96	dendritic SnS <sub>2</sub>	16
1T-TaS <sub>2</sub>	Au	0.5 M H <sub>2</sub> SO <sub>4</sub>	~205	72	1T phase	17
2H-TaS <sub>2</sub>	Au	0.5 M H <sub>2</sub> SO <sub>4</sub>	65–150	33	2H phase	18
TaS <sub>2</sub> -N <sub>2</sub> H <sub>4</sub>	SiO <sub>2</sub> /Si	0.5 M H <sub>2</sub> SO <sub>4</sub>	~400	76	Intercalate-d flake	19
3DHP-Mo <sub>2</sub> C	GC	0.5 M H <sub>2</sub> SO <sub>4</sub>	97	60	Porous framework	20
Mo <sub>2</sub> C NP	GC	0.5 M H <sub>2</sub> SO <sub>4</sub>	144	55	Nanoparticle	21
		1.0 M KOH	100	65		
Mo <sub>2</sub> C@NC	GC	0.5 M H <sub>2</sub> SO <sub>4</sub>	121	67	Nanodots	22
Mo <sub>2</sub> C NT	GC	0.5 M H <sub>2</sub> SO <sub>4</sub>	172	62	Nanoparticle	23
		1.0 M KOH	112	55		

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